2nd Announcement and Call for Papers

Photomask Japan 2023 Digital Forum

April 25(Tue.) - 27(Thu.), 2023

The 29th Symposium on Photomask and Next Generation Lithography Mask Technology

Abstract Due Date: November 30 (Wed.), 2022
＊Camera-Ready Abstract Submission is not required.
Manuscript Due Date: March 31 (Fri.), 2023
These are ***FIRM!***
Manuscripts are required of all accepted applicants and must be submitted in English.

Symposium Chair: **Prof. Takeo Watanabe, University of Hyogo (Japan)**
Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

Papers are solicited on the following and related topics:

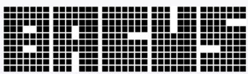
- **Materials for photomasks**
- **Fabrication process steps and equipment for photomasks (developing, etching, cleaning etc.)**
- **Photomask writing tools and technologies including multi-beam EB writer**
- **Tools and technologies for metrology/ inspection/ repair**
- **Technologies and Infrastructures for EUVL/ NIL/ FPD masks**
- **EDA, MDP, curvilinear ILT and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and multiple patterning**
- **Photomask-related lithography technologies**
- **NGL mask technologies and their applications: DSA and others**
- **Strategy and business challenges: cost, cycle time and total mask solutions**
- **Patterning technologies for semiconductor and electronic devices**
- **Semiconductor manufacturing technologies**
- **eBeam direct writing and eBeam lithography technologies**
- **Utilizing AI technologies for the efficiency of R&D and HVM**
- **Legacy tools for middle and low-end masks**
- **Photomask and lithography related technologies in academia**

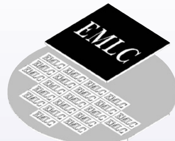
All abstracts are to be registered electronically via the PMJ website to get the qualification for abstract submission to the conference.

Organized by

SPIE.

Co-organized by





For more information, contact:
Photomask Japan Secretariat
c/o JTB Communication Design, Inc.
Celestine Shiba Mitsui Bldg., 3-23-1 Shiba,
Minato-ku, Tokyo 105-8335, Japan
E-mail : pmj@jtbcom.co.jp
https://www.photomask-japan.org

SPIE Proceedings Coordinator
E-mail: JennyW@spie.org

See the next page for more information ↓

PMJ website will begin accepting abstracts: October 3 (Mon.), 2022

＊**Abstract Due Date:** November 30 (Wed.), 2022

＊**Manuscript Due Date:** March 31 (Fri.), 2023

Abstracts will be published in **Digest of Papers**, which will be available on the website.

All abstracts must be registered electronically with the PMJ website at: **https://www.photomask-japan.org**

If electronic submission is not possible then authors are asked to contact the Photomask Japan Secretariat before the abstract due date.

All authors are strongly encouraged to submit their abstract by November 30, 2022.

Please note : the electronic abstract submission system will close on time and late abstracts will not be accepted.

And Manuscripts are required of all accepted applicants and must be submitted in English.

Please note: *This information is subject to change without notice. PMJ requests all prospective authors to regularly check the PMJ website for updates.*

To submit an abstract:

Abstracts must be written and presented **in English.**

All abstracts must be submitted electronically **in a PDF file** via the symposium website. No fax and e-mail submission are accepted.

Abstract Submission Information:

https://www.photomask-japan.org

You will receive your reference number in return by e-mail when the submission succeeded. If you do not receive a response within 24 hours, please contact the Abstract Submission Office.

All abstracts must contain the following information:

1. Title of Abstract:
The title of the abstract should be written in Times New Roman, bold, 16pt, centered. Initial letters of each word should be capitalized.

2. Names of All Authors:
Author's name and affiliation spelled out completely in Times New Roman, 12pt, centered. Initial letters of each word must be capitalized. If there are several authors or affiliations, Presenting Author should be listed first and the related numbers should be given using superscripts. Also include the mailing address, and email address.

3. Abstract Text and Figures:
Text should be approximately 250 words, not exceeding one A4 page including figures.

4. Keywords:
List maximum of five keywords. Please choose at least one keyword for your abstract.

Notification of Acceptance:

The Photomask Japan Program Committee will review all contributed abstracts. Applicants will be notified of acceptance or rejection by e-mail no later than the end of January 2023.

Photomask and Lithography related Technology in Academia

PMJ offers an opportunity for university students or postdoctoral researchers to present their works on mask / lithography technology fields.
Those who wish to present their works are asked to submit an abstract via online in accordance with the guidance of the Abstract Submission page on the website.

Session Scope: Mask technology, lithography technology and applications

Object Presenter: Applicants should be university students or postdoctoral researchers

Registration Fee: Free for Academia

Digital Forum Operation (tentative)

Sessions:
- Oral session: Online live presentation and Q&A via zoom
  (Audiences will freely ask questions using zoom Q&A box.)
- Poster session: Online live presentation and Q&A in zoom break-out rooms
  (Audiences will orally ask questions in zoom break-out rooms.)

Presentation Materials:
- The detailed guidelines will be available later.

Abstract Submission Office:
Photomask Japan Secretariat
c/o JTB Communication Design, Inc.
Celestine Shiba Mitsui Bldg., 3-23-1 Shiba, Minato-ku, Tokyo 105-8335, Japan
E-mail : pmj-p@jtbcom.co.jp
https://www.photomask-japan.org